Amendments to the Specification:

Please add the following new paragraph, after the paragraph ending at page 7, line 22:

--Figure 9: Schematic illustration of a particle formation vessel which may be employed in the process of the invention.--

Please add the following new paragraph, after the paragraph ending at page 9, line 23:

-- Figure 9 is a schematic illustration of a particle formation vessel **10** which may be employed in the process of the invention. In such figure, rotary agitator **11** comprising an impeller **12** having an impeller surface **s** and an impeller diameter **d**, and a zone **13** is illustrated located within a distance of one impeller diameter from the surface of the impeller of the rotary agitator. A bulk mixing zone **14** is located at distances greater than one impeller diameter from the surface of the impeller. A first feed stream comprising a solvent and the desired substance dissolved therein may be introduced into the agitated particle formation vessel through a first feed stream introduction port **15**, and a second feed stream comprising the supercritical fluid may be introduced into the agitated particle formation vessel through a second feed stream introduction port **16**. The first and second feed stream introduction ports are located in zone **13** within a distance of one impeller diameter from the surface of the impeller **12** of the rotary agitator **11** such that the first and second feed streams may be introduced into a highly agitated zone of the particle formation vessel and the first feed stream is dispersed in the supercritical fluid by action of the rotary agitator, allowing extraction of the solvent into the supercritical fluid, and precipitation of particles of the desired substance in the particle formation vessel. Supercritical fluid, solvent and the desired substance may be exhausted from the particle formation vessel through an outlet port **17**.--

Please replace the previously rewritten paragraph beginning on page 14, line 1 with the following rewritten paragraph:

--Very fine particles obtained in accordance with the invention may further be printed, coated, or otherwise deposited on a substrate upon expansion of the supercritical fluid mixture in processes similarly as described in

concurrently filed, ~~copending,~~ commonly assigned USSNs 10/815,026 (now USP 7,223,445) and 10/815,010 (now USP 7,220,456), the disclosures of which are incorporated by reference herein. Since the process of the present invention produces fine powder that is comparable to those produced by RESS techniques, RESS –based thin film deposition techniques (including method and apparatus, with minor changes to account for low level of organic solvent present in the supercritical mixture) may also be employed for the particles produced by the present invention. For example, after formation of particles in a particle formation vessel by SAS type process in accordance with the invention, the resulting mixture of very fine (less than 100 nanometers, preferably less than 50 nanometers, most preferably less than 10 nanometers) precipitated particles and compressed supercritical fluid may be expanded under controlled conditions and thin films of the particles may be coated on a substrate, similarly as in the RESS (and other similar) type coating processes described in U.S. Patent Nos. 4,582,731, 4,734,227, 4,734,451, 4,970,093, 4,737,384, 5,106,650, and Fulton et al., Polymer, Vol. 44, 3627-3632 (2003), the disclosures of which are incorporated by reference herein. Condensation of solvent from the supercritical fluid, solvent, and precipitated solute mixture upon expansion of the mixture may be avoided or minimized, if desired, by selection of a solvent with sufficiently high vapor pressure, and/or control of the temperature and pressure of the expansion chamber.--